

SubD3  
Q2

3. (Four times amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said pixel electrode is formed of a transparent conductive film, and

wherein said reflection layer formed of a dielectric multi-layer film is provided under said pixel electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied by  $\lambda/4$ , wherein  $\lambda/4$  satisfies a relation of  $nd = \lambda/4$ , where  $n$  is a refractive index,  $d$  is a film thickness, and  $\lambda$  is a center wavelength.

SubD4  
Q3

5. (Four times amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said switching element is connected to a capacitance,

wherein said capacitance comprising a common electrode formed of a transparent conductive film, a dielectric film formed on said common electrode, and said pixel electrode formed of a transparent conductive film formed on said dielectric film,

wherein said reflection layer formed of a dielectric multi-layer film is provided below said common electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied by  $\lambda/4$ , wherein  $\lambda/4$  satisfies a relation of  $nd = \lambda/4$ , where  $n$  is a refractive index,  $d$  is a film thickness, and  $\lambda$  is a center wavelength.

SubD5  
Q4

8. (Four times amended) A method of manufacturing a liquid crystal display device, comprising the steps of:  
forming a switching element formed on a substrate;  
a reflection layer formed of a dielectric multi-layer film above said switching element; and,